

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S25	11	substrate.clm. and exposure.clm. and acid.clm. and diffusion.clm. and dissolving.clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S26	0	"118"/\$.ccls. and (pivotal with shift) and (exposure) and (acid with dissolving with diffusion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S27	0	"396"/\$.ccls. and (pivotal with shift) and (exposure) and (acid with dissolving with diffusion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S28	34	"396"/\$.ccls. and (pivotal with shift) and (exposure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:11
S29	3	"430"/\$.ccls. and (pivotal with shift) and (exposure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S30	1	"438"/\$.ccls. and (pivotal with shift) and (exposure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S31	1	"118"/\$.ccls. and (pivotal with shift) and (exposure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S32	0	"118"/\$.ccls. and (pivotal with shift) and (photoresist) and time and control	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05

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S33	3	(pivotal with shift) and (photoresist) and time and control	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S34	18	(developing with time with control) and (photoresist) and "118"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S35	14	(developing with time with control) and (correlation) and "118"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S36	121	(118/698).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/05 11:15
S37	175	(118/699).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/05 11:01
S38	161	(118/682).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/04 23:05
S39	524	(118/665).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/04 23:05
S40	92	(118/702).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/04 23:05

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S41	198	(118/704).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/04 23:05
S42	2	("6281145").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/04 23:05
S43	5	(("6869234") or ("6749351") or ("6752544") or ("6656277") or ("6692165")).PN.	US-PGPUB; USPAT	OR	OFF	2007/11/08 14:19
S44	7	"substrate treating method and apparatus"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S45	3	wafer and exposure and (acid with diffusion with dissolving)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/04 23:05
S47	2	("5089305" "6541063").PN. OR ("7094440").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/11/05 11:03
S48	376	(118/668).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/05 11:16
S49	342	(118/697).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/05 11:25
S50	113	(700/306).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/11/05 13:18

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S51	12	("4715921" "4717461" "4835699" "5495417" "5914879" "5933526").PN. OR ("6258169").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/11/05 11:34
S52	5963	cluster with tool	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/06 12:36
S53	51136	"700"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/05 13:19
S54	1489864	process\$4 with time	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/05 13:19
S55	212	S52 and S53 and S54	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/05 15:32
S56	0	(cluster with tool) and (develop\$4 with time with derivation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/06 22:11
S57	56	(develop\$4 with time with derivation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/06 21:41
S58	14	(time with derivation) and (semiconductor with wafer with processing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/06 21:49

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S60	103	koch.xp.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/06 21:49
S61	4	((cluster with tool) and (develop\$4 with time with calculate\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/06 22:12
S62	380	((cluster with tool) and (time with calculate\$4) and (develop\$4 or photoresist))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/06 22:12
S63	112	((cluster with tool) and (time with calculate\$4) and ((develop\$4 or photoresist) with time))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/08 12:23
S64	7331	((coating or dispensing) with time) and (controller or computer or processor) and (nozzle)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/08 14:13
S65	615	((coating or dispensing) with time) and (controller or computer or processor) and (nozzle) and ((calculating or calibrating or deriving or calculate or calibrate or derive) with time)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/08 14:15
S66	46	((coating or dispensing) with time) and (controller or computer or processor) and (nozzle) and ((calculating or calibrating or deriving or calculate or calibrate or derive) with time) and (semiconductor with wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/08 16:49
S67	1	("7094440").PN.	US-PGPUB; USPAT	OR	OFF	2007/11/08 14:28
S68	1	("6902762").PN.	US-PGPUB; USPAT	OR	OFF	2007/11/08 14:28

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S69	19	((coating or dispensing) with recipe) and (controller or computer or processor) and (nozzle) and ((calculating or calibrating or deriving or calculate or calibrate or derive) with time) and (semiconductor with wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/08 21:04
S70	24	((coating or dispensing) with recipe) and (controller or computer or processor) and ((calculating or calibrating or deriving or calculate or calibrate or derive) with time) and (semiconductor with wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/08 22:59